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Autore	Kohler J. M (J. Michael), <1956->
Titolo	Etching in microsystem technology [[electronic resource] /] / Michael Kohler ; translated by Antje Wiegand
Pubbl/distr/stampa	Weinheim ; ; New York, : Wiley-VCH, c1999
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Descrizione fisica	1 online resource (386 p.)
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Soggetti	Masks (Electronics) Microlithography Plasma etching Electronic books.
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Description based upon print version of record.
Nota di bibliografia	Includes bibliographical references ([345]-360) and index.
Nota di contenuto	Etching in Microsystem Technology; Preface; Contents; Table of Contents; Symbols; Abbreviations; 1 Introduction; 2 Distinctive Features of Microtechnical Etching; 2.1 Etching as a Fashioning Method; 2.1.1 Limits of Additive Microtechnical Pattern Generation; 2.1.2 Subtractive Pattern Generation; 2.2 Etch Rate and Selectivity; 2.2.1 Etch Rate and Time Request; 2.2.2 The Etching Process; 2.2.3 Transport Processes; 2.2.4 Process Velocities; 2.3. Isotropic and Anisotropic Etching; 2.4 Edge Geometry and Roughness; 2.4.1 Deviations from Ideal Geometry; 2.4.2 Flank Geometry in Isotropic Etching 2.4.3 Fabrication of Low Slope Angles by Isotropic Etching2.4.4 Flank Geometries in Anisotropic Etching; 2.4.5 Setting the Flank Geometry by Partial Anisotropic Etching; 2.5 Accuracy; 2.6 Monitoring of Etching Processes; 3 Wet-Chemical Etching Methods; 3.1 Etching at the Interface Solid-Liquid; 3.2 Preparation of the Surface; 3.2.1 Surface Condition; 3.2.2 Cleaning; 3.2.3 Digital Etching; 3.3 Etching of Dielectric Materials; 3.3.1 Wet Etching by Physical Dissolution; 3.3.2

Wet-Chemical Etching of Non-Metals; 3.4 Etching of Metals and Semiconductors; 3.4.1 Outer-Currentless Etching 3.4.2 Selectivity in Outer-Currentless Etching 3.4.3 Etching of Multilayer Systems Forming Local Elements; 3.4.4 Geometry-Dependent Etch Rates; 3.4.5 Geometry-Dependent Passivation; 3.4.6 Electrochemical Etching; 3.4.7 Photochemical Wet Etching; 3.4.8 Photoelectrochemical Etching(PEC); 3.5 Crystallographic Etching; 3.5.1 Chemical Wet-Etching of Monocrystalline Surfaces; 3.5.2 Anisotropic Etching of Monocrystalline Metals; 3.5.3 Anisotropic Etching of Silicon; 3.5.4 Anisotropic Electrochemical and Photoelectrochemical Etching; 3.5.5 Porous Silicon 3.6 Anisotropic Etching of Compound Semiconductors 3.6 Preparation of Free-Standing Micropatterns; 3.6.1 Surface Micromachining; 3.6.2 Bulk Micromachining; 3.6.3 Porous Silicon as Sacrificial Material; 4 Dry-Etching Methods; 4.1 Removal at the Interface Solid-Gas; 4.2 Plasma-Free Etching in the Gas Phase; 4.2.1 Plasma-Free Dry-Etching with Reactive Gases; 4.2.2 Photo-Assisted Dry Etching with Reactive Gases; 4.2.3 Directly Writing Micropatterning by Laser Scanning Etching; 4.2.4 Electron-Beam-Assisted Vapour Etching; 4.3 Plasma Etching Methods 4.3.1 Material Removal by Reactions with Plasma Species 4.3.2 Plasma Generation; 4.3.3 Plasma Etching in the Barrel Reactor; 4.3.4 Plasma Etching in the Down-Stream Reactor; 4.3.5 Plasma Etching in the Planar-Plate Reactor; 4.3.6 Magnetic-Field-Enhanced Plasma Etching; 4.3.7 Plasma Etching at Low Pressure and High Ion Density; 4.3.8 Forming of Etch Structures in Plasma Etching; 4.3.9 Geometry Influence on Plasma Etching; 4.3.10 Plasma Jet Etching (PJE); 4.3.11 Applications of Plasma Etching; 4.4 Etching Methods with Energized Particles; 4.4.1 Sputter-Etching; 4.4.2 Reactive Ion Etching (RIE) 4.4.3 Magnetic-Field-Enhanced Reactive Ion Etching (MERIE)

Sommario/riassunto

Microcomponents and microdevices are increasingly finding application in everyday life. The specific functions of all modern microdevices depend strongly on the selection and combination of the materials used in their construction, i.e., the chemical and physical solid-state properties of these materials, and their treatment. The precise patterning of various materials, which is normally performed by lithographic etching processes, is a prerequisite for the fabrication of microdevices. The microtechnical etching of functional patterns is a multidisciplinary area, the basis for the etching p

2. Record Nr.	UNINA9910974767203321
Autore	Hamilton Nigel
Titolo	Biography : a brief history / / Nigel Hamilton
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ISBN	9780674264267 0674264266 9780674038226 0674038223
Descrizione fisica	1 online resource (358 p.)
Classificazione	EC 7419
Disciplina	907.2
Soggetti	Biography as a literary form Biography - History
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Bibliographic Level Mode of Issuance: Monograph
Nota di bibliografia	Includes bibliographical references (p. 315-321) and index.
Nota di contenuto	Frontmatter -- Contents -- Illustrations -- Prologue -- 1. Evolutionary Biography -- 2. Hagiography -- 3. The Renaissance of Biography -- 4. Victorian Pseudobiography -- 5. The Early Twentieth Century -- 6. The Rise of Film -- 7. The People's War -- 8. Death of the Author -- 9. New Directions -- 10. Biography Comes of Age -- 11. Biography on Trial -- 12. The Miner's Canary -- 13. Biography Today -- Epilogue -- Notes -- Bibliography -- Acknowledgments -- Index
Sommario/riassunto	For what purpose and for whom has biographical pursuit endured, and how does it play such a contested, popular role in contemporary Western culture, from biopics to blogs, memoirs to docudramas? Award-winning biographer Hamilton addresses these questions in an incisive and vivid narrative that will appeal to students of human nature and self-representation across the arts and sciences.

3. Record Nr.	UNINA9910893065003321
Titolo	Alazet : revista de filologia
Pubbl/distr/stampa	Huesca, : Instituto de Estudios Altoaragoneses, 1989-
Soggetti	Spanish philology Spanish language - Spain - Huesca (Province) Spanish language - Spain - Aragon Spanish language Filologie Spaans Dialecten Periodicals. Spain Aragon Spain Huesca (Province)
Lingua di pubblicazione	Spagnolo
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